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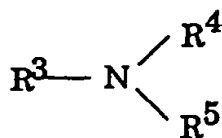
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(54) Title: POLISHING LIQUID COMPOSITION



(II)

prising an amine compound represented by general formula (II) wherein R<sup>3</sup> is a linear or branched alkyl group having 4 to 18 carbon atoms, a linear or branched alkenyl group having 4 to 18 carbon atoms, an aryl group having 6 to 18 carbon atoms, and an aralkyl group having 7 to 18 carbon atoms; each of R<sup>4</sup> and R<sup>5</sup>, which may be identical or different, is hydrogen atom, a linear alkyl group having 1 to 8 carbon atoms or a branched alkyl group having 3 to 8 carbon atoms, or a group represented by H-(OR<sup>6</sup>)<sub>2</sub>, wherein R<sup>6</sup> is a linear alkylene group having 1 to 3 carbon atoms, or a branched alkylene group having 3 carbon atoms; and Z is a number of 1 to 20, and/or a salt thereof, an etching agent, and water.

(57) Abstract: A polishing liquid composition for polishing a surface to be polished comprising an insulating layer and a metal layer selected from (1) to (3): (1) the polishing liquid composition comprising a compound having a structure in which each of two or more adjacent carbon atoms has a hydroxyl group in a molecule, and water; (2) the polishing liquid composition comprising an aliphatic carboxylic acid having 7 to 24 carbon atoms and/or a salt thereof, an etching agent, and water; (3) the polishing liquid composition comprising

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